

LINTON



Technical Trend of Advanced PV Ingot & Wafer Production

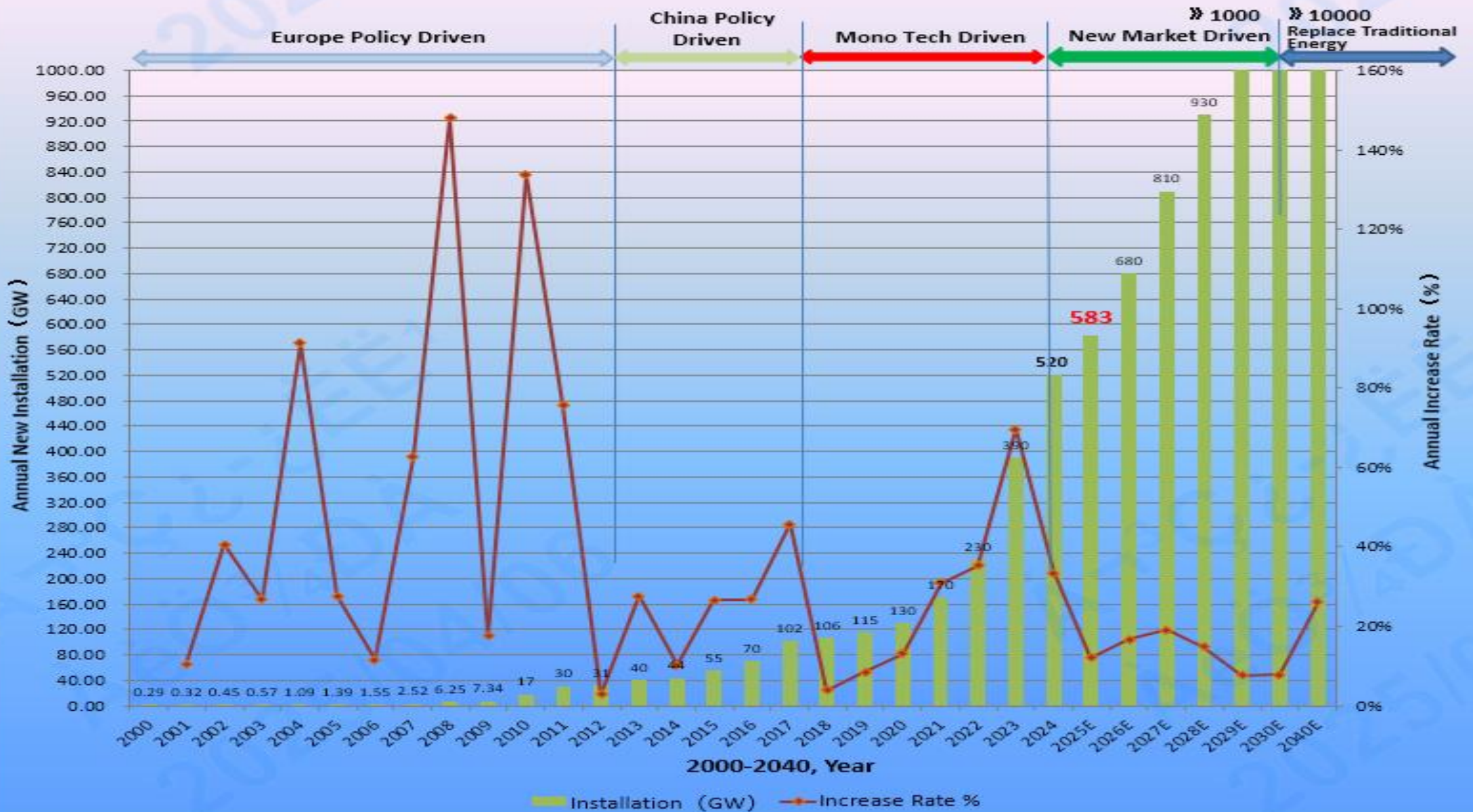
Dr. Zhixin Li
Linton Crystal Technologies
Linton Technologies Group





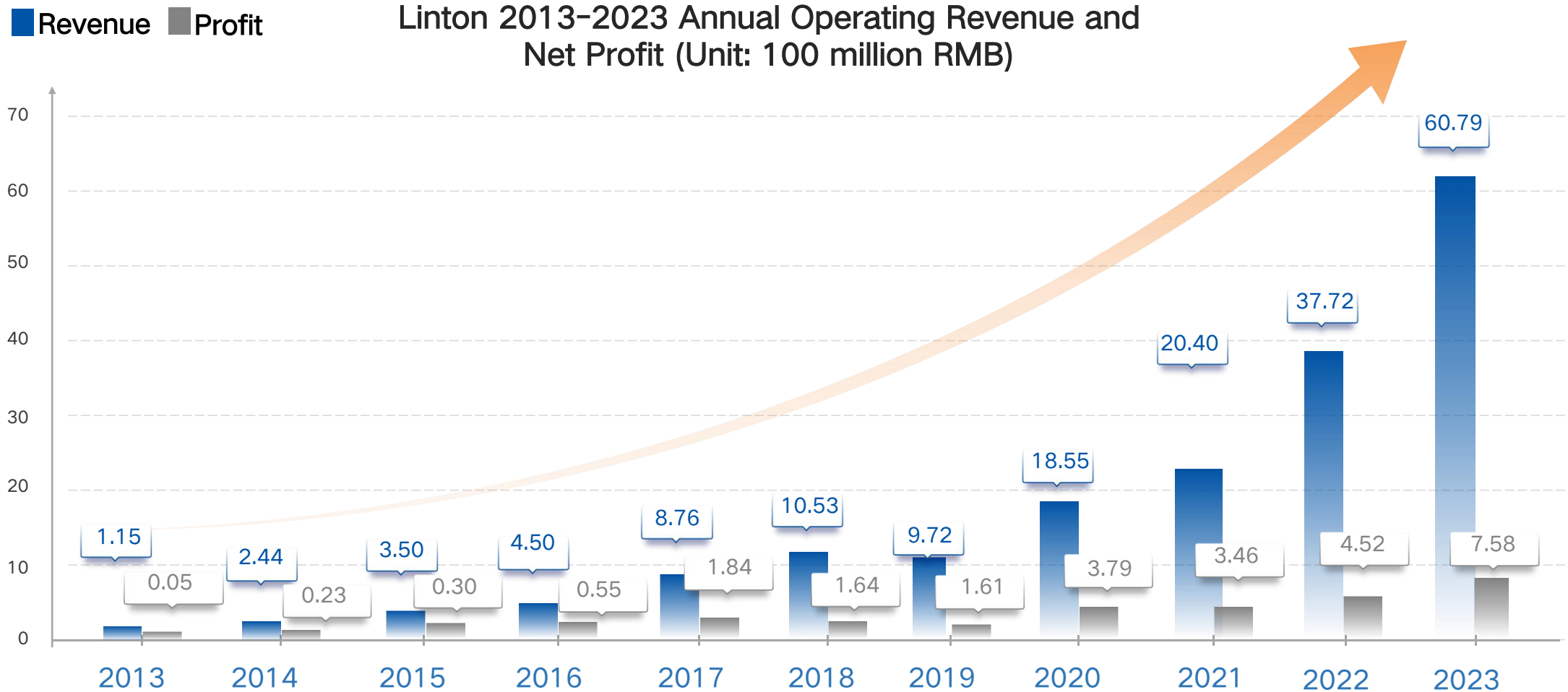
- 01 PV Industry in the past 25 years
- 02 Growth of Linton
- 03 Critical Technology Path
- 04 New Directions

2000-2040 Global PV Annual New Installation Capacity



Sustained Growth Trusted Assurance

Total assets in 2023 reached 1.743 billion



Linton has service teams in the USA, Singapore, Russia, India, and Malaysia, with operations spanning 18 countries and regions worldwide.



Wuxi R&D and Manufacturing Base



- PV Crystal growing, si wafer cleaning, cells & modules equipment;
- Semi-conductor Si, Ge crystal growing , crystal growing equipment
- SiC semiconductor powder sythensisi, crystal growing and processing equipment;
- Gallium oxide, sapphire crystal growth, crystal processing equipment

Dalian R&D and Manufacturing Base



- Si microwave crushing equipment;
- PV crystal and wafer processing equipment;
- Semiconductor Si, SiC, Sapphire slicing equipment;
- Automation and smart factory solution

U.S. Technology R&D Base



- Extended 70 years of experience in the design and manufacture of monocrystalline furnace and crystal growth;
- PV and monocrystalline furnace equipment R &D base in the US
- Advanced R&D of crystal growth
- International Marketing

Vietnam Production and Manufacturing Base



- PV equipment manufacturing
- Single cyrstal furnace
 - Slicer
 - Machining equipment
 - Other equipment

Wuxi Base
2,000,000+
Square Feet

Dalian Base
1,200,000+
Square Feet

Crystal Grower Capacity
16000+
Set/Year

Slicer & Ingot Machining
6000+
Set/Year

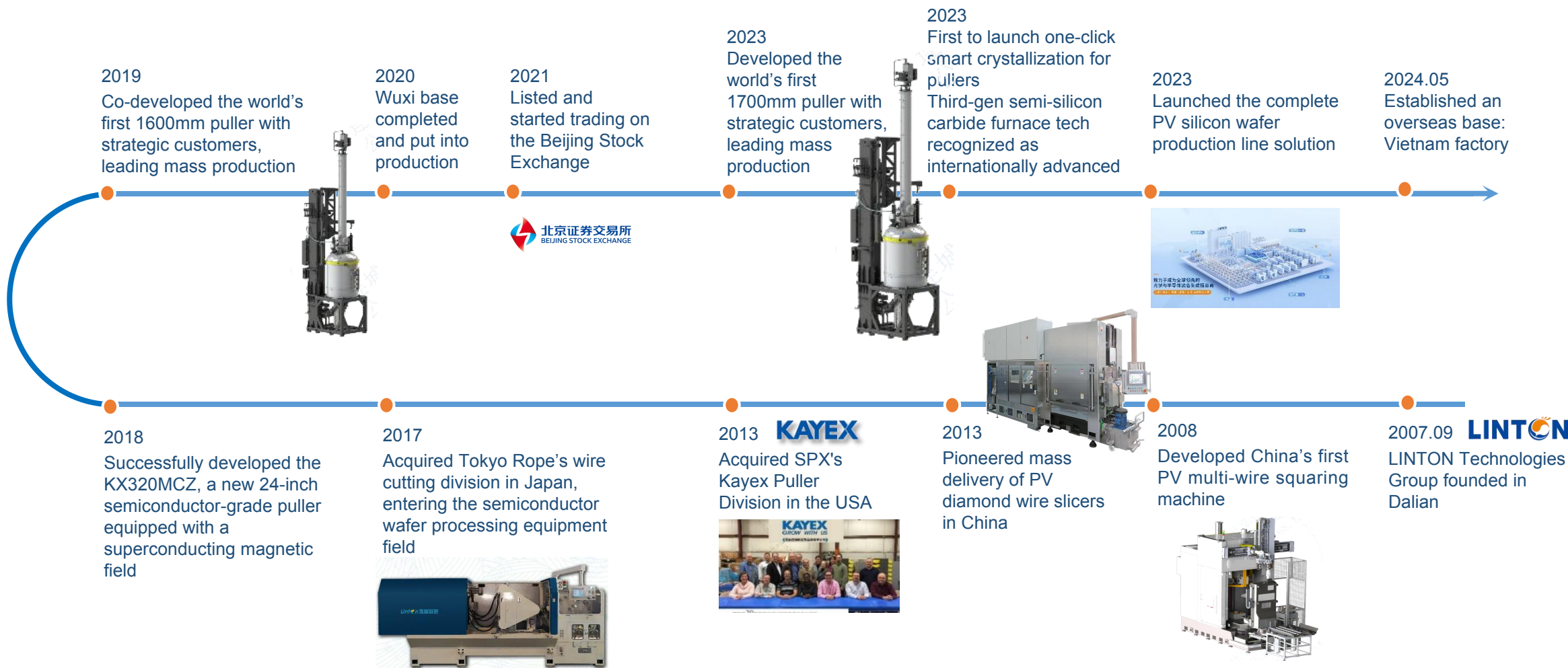
Equivalent to
300+GW
Annual Capacity



Wuxi Facility of Linton

Over 2,000,000 Square Feet
Floor Space

Group Development Timeline

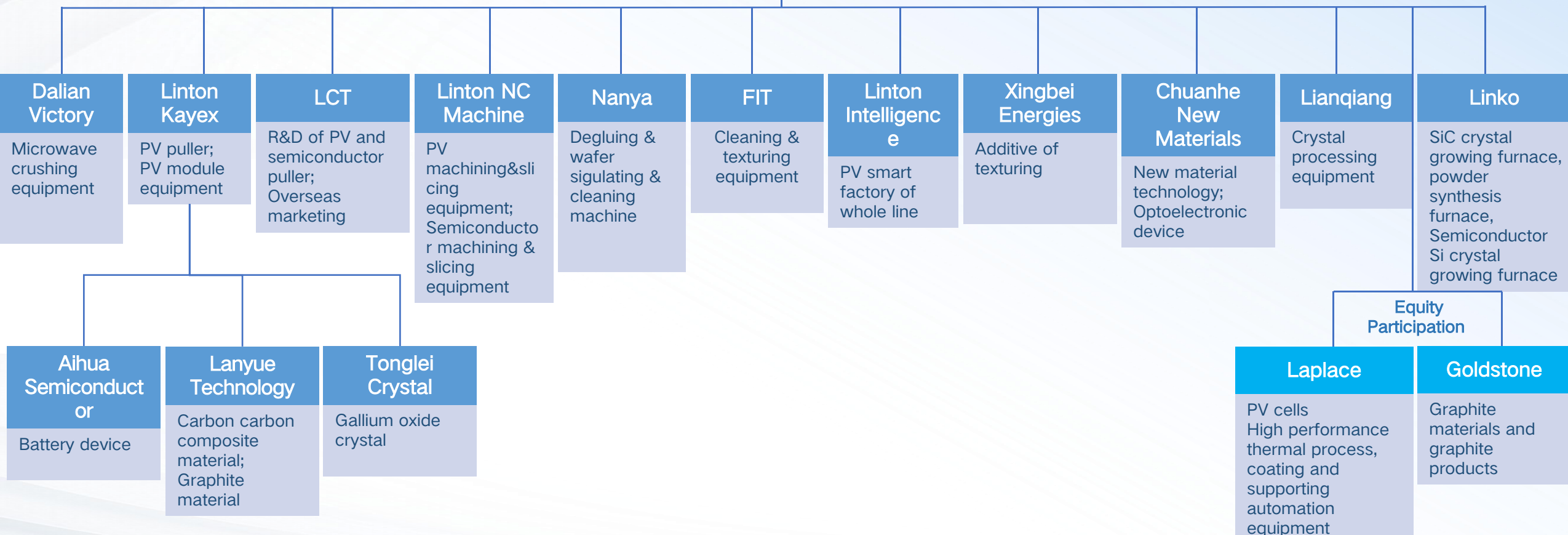




689 项
国内外专利

2
全资子公司

24
控股子公司



To become a strong player in PV industry, it is very important to select the right technical path. Linton made 3 critical decisions in the past 15 years:

First critical decision:

Selected mono-crystal technology while most people in PV industry believed in multi-crystal technology

Linton Solar CZ Furnaces 连城光伏单晶炉系列

LINTON



CG3000
TankID 580mm
RC ID 220mm
Height 4000mm

CG6000
TankID 760mm
RC ID 280mm
Height 5700mm

KX100
TankID 900mm
RC ID 300mm
Height 7000mm

KX150
TankID 1100mm
RC ID 350mm
Height 8000mm

KX170
TankID 1200mm
RC ID 350mm
Height 9000mm

KX240
TankID 1300mm
RC ID 350mm
Height 10000mm

KX280
TankID 1400mm
RC ID 350mm
Height 11000mm

KX380
TankID 1600mm
RC ID 450mm
Height 13800mm

**KX380PV
Crystal Grower**





Typical silicon mono-crystals produced with a Linton CZ furnace

G12

Length > 5 meters, Weight > 800 kg, Diameter = 301 mm

M10

Length > 7 meters, Weight > 800 kg, Diameter = 254 mm



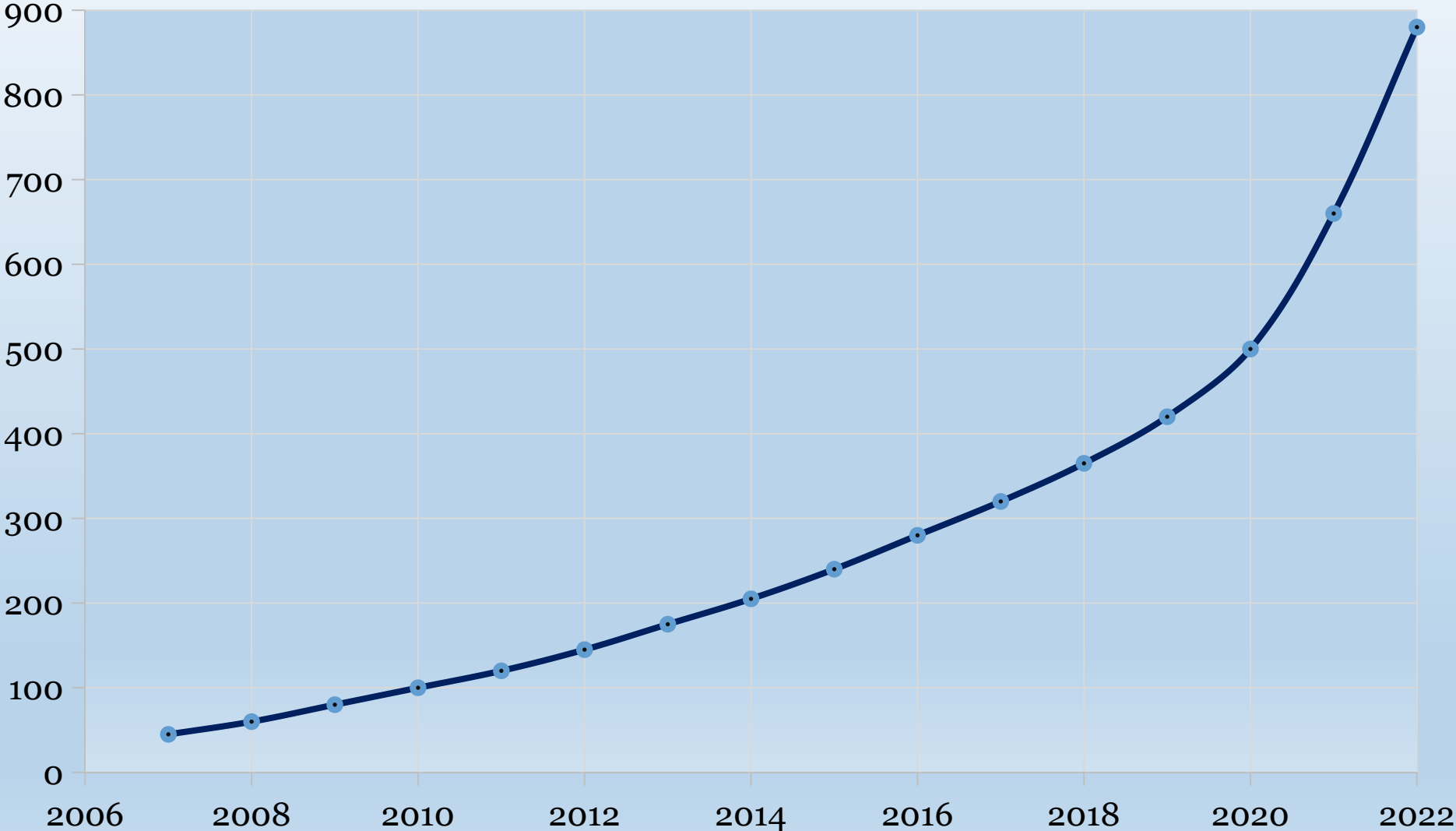
Increase of Crucible size 坩埚尺寸不断增大



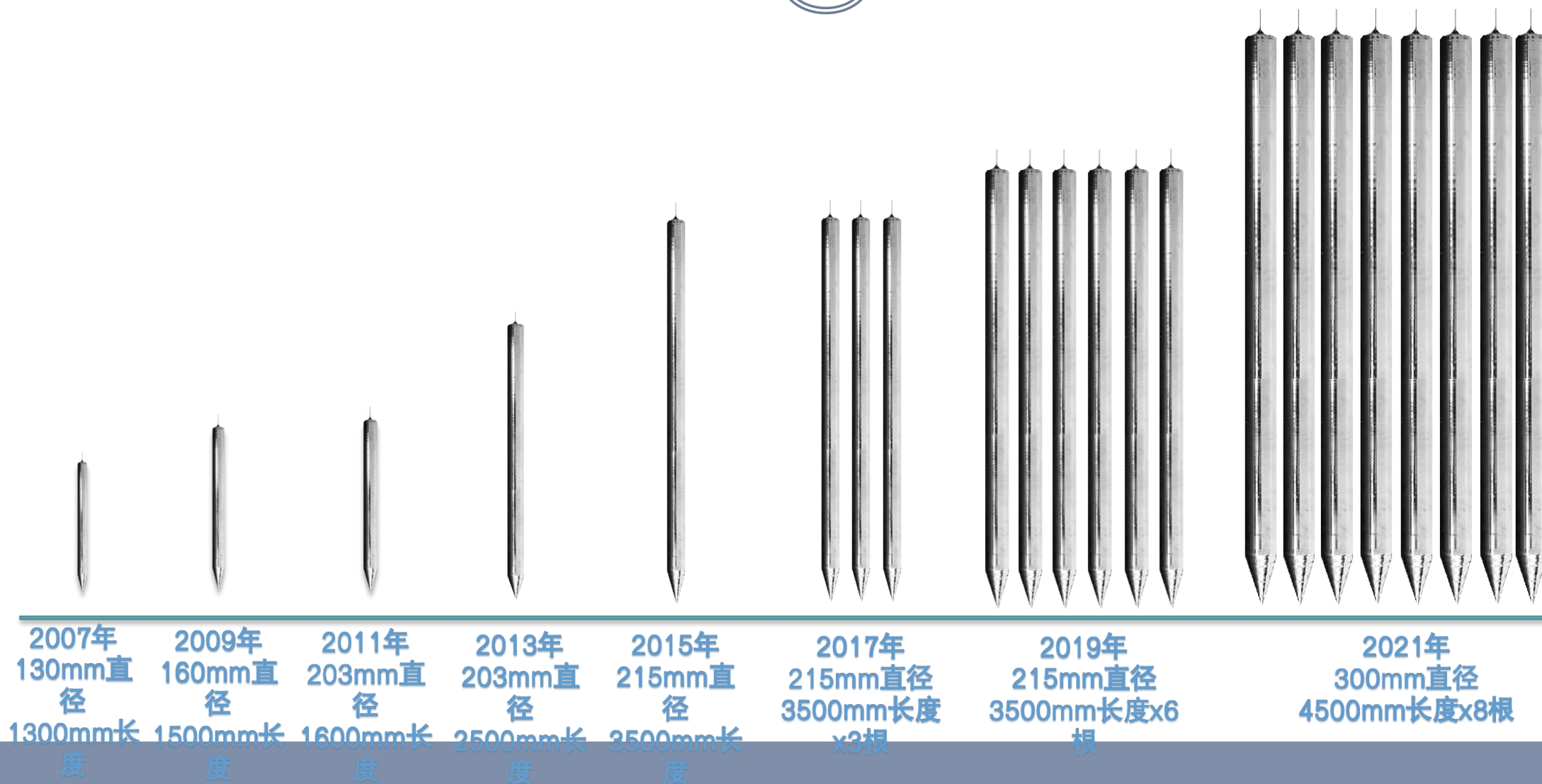
Trend of CZ Crystal Growth Charge Size

单晶炉装料量变化趋势

kg



Comparison of Mono-Crystal Ingots from a single Run 单一炉次生产的单晶硅棒尺寸比较



To become a strong player in PV industry, it is very important to select the right technical path. Linton made 3 critical decisions in the past 15 years:

Second critical decision:

Being the first to promote diamond wire wafer slicing technology while most people in PV industry believed in slurry cutting technology

QP850 金刚线多线切片机

QP850 Diamond Wire
Multi-wire Wafer Slicing Machine



基本性能参数

加工能力

装载长度 (mm) 最大850 单排装料

截面尺寸 (mm) 最大166 × 166

切片厚度 (mm) 0.12 ~ 0.20

Basic Performance Parameter

Processing Ability

Loading length (mm) Max 850 material loading on single row

Workpiece size (mm) Max 166 × 166

Wafer slicing thickness (mm) 0.12~0.20



Linton Diamond Wire Slicer.mp4

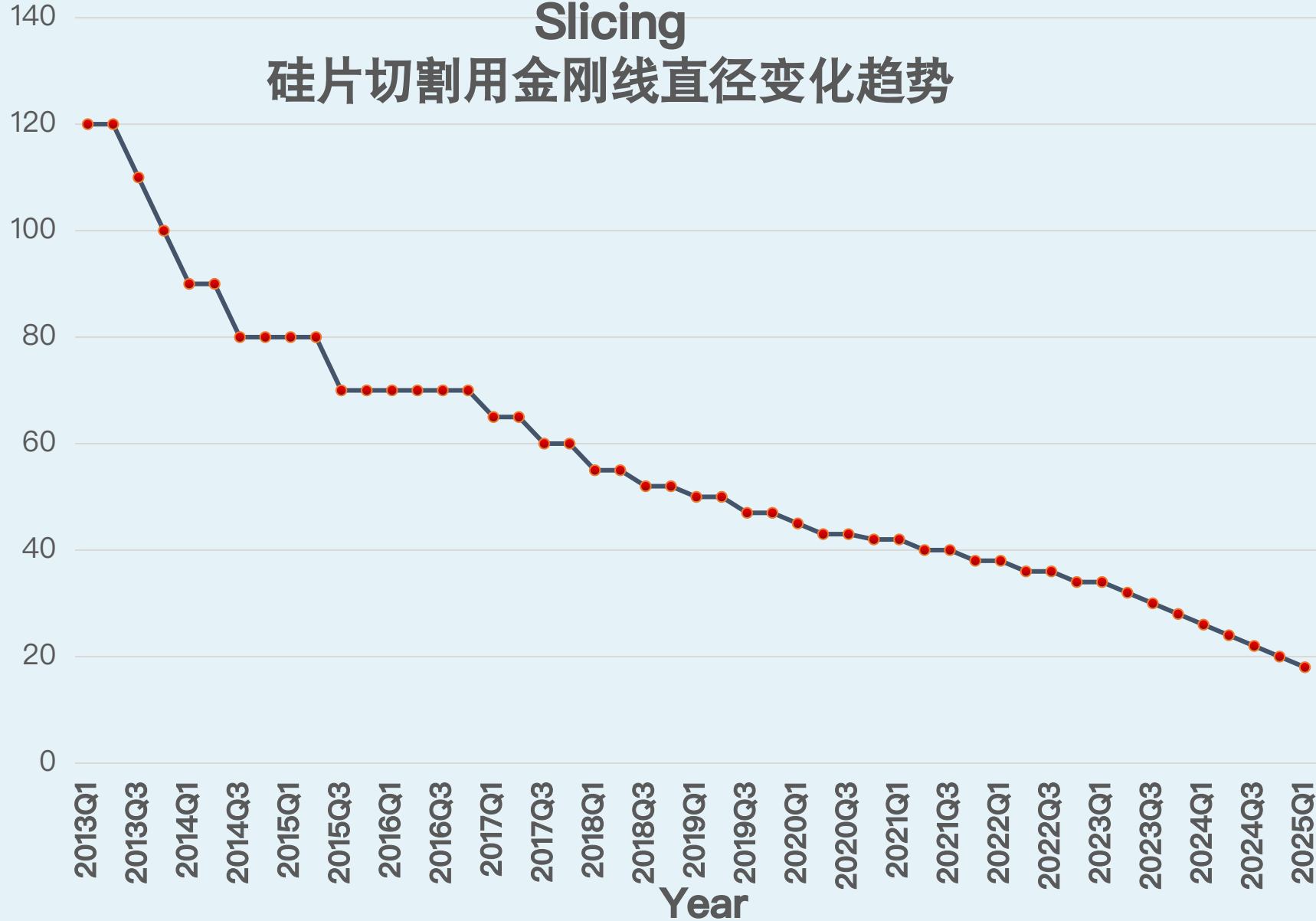
Linton DW Slicer Performance

- 45 meters/sec wire speed
- Capable of using 28 micron steel wire, 18 micron tungsten wire
- > 1,200,000 wafers per month per slicer
- Slicing cost < \$0.02 per wafer

Trend of DW Wire Diameter for Silicon Wafer Slicing

硅片切割用金刚线直径变化趋势

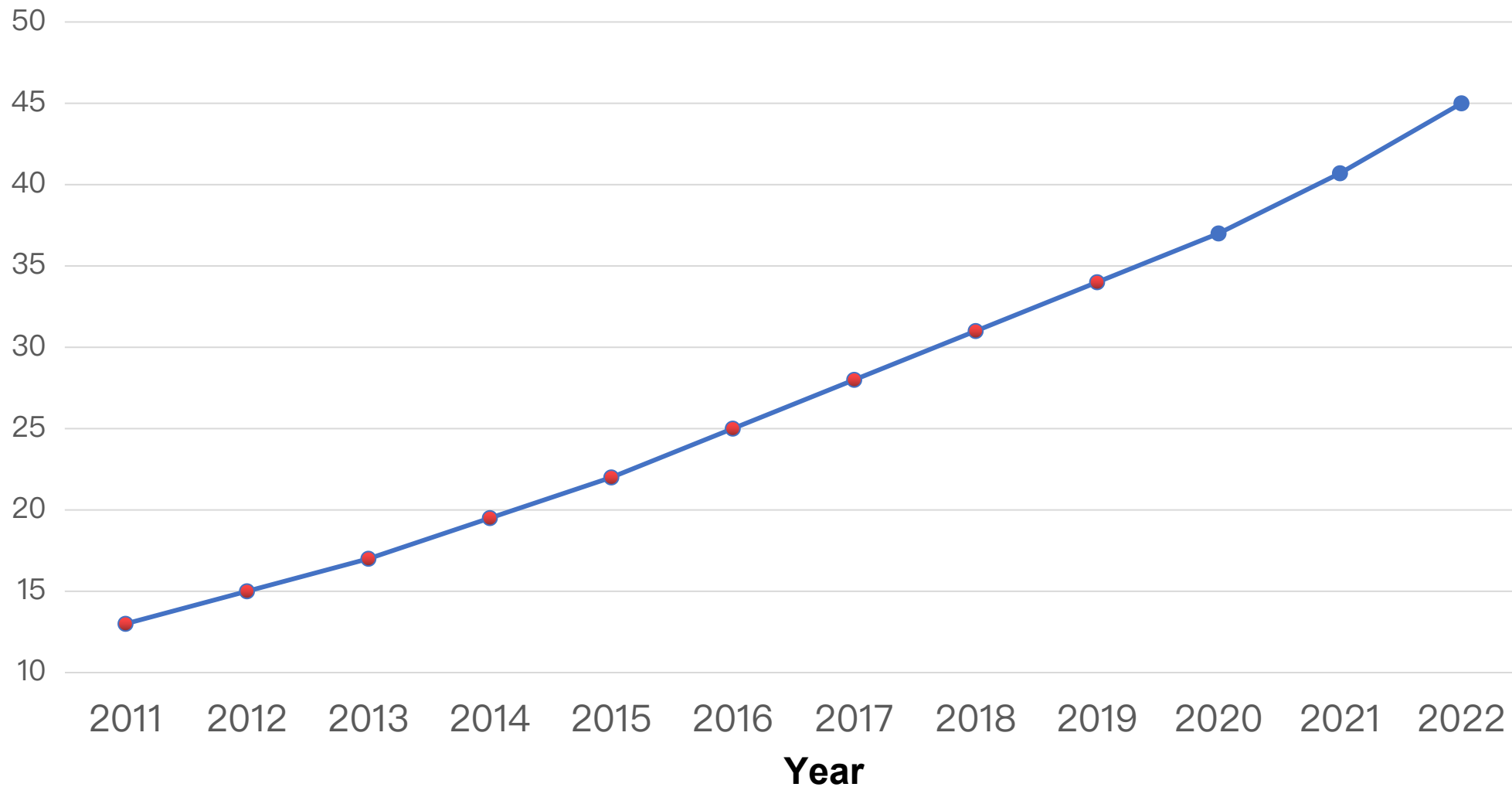
芯线直径 Core Wire Diameter (Micro-Meter)



金刚线切割线速变化趋势

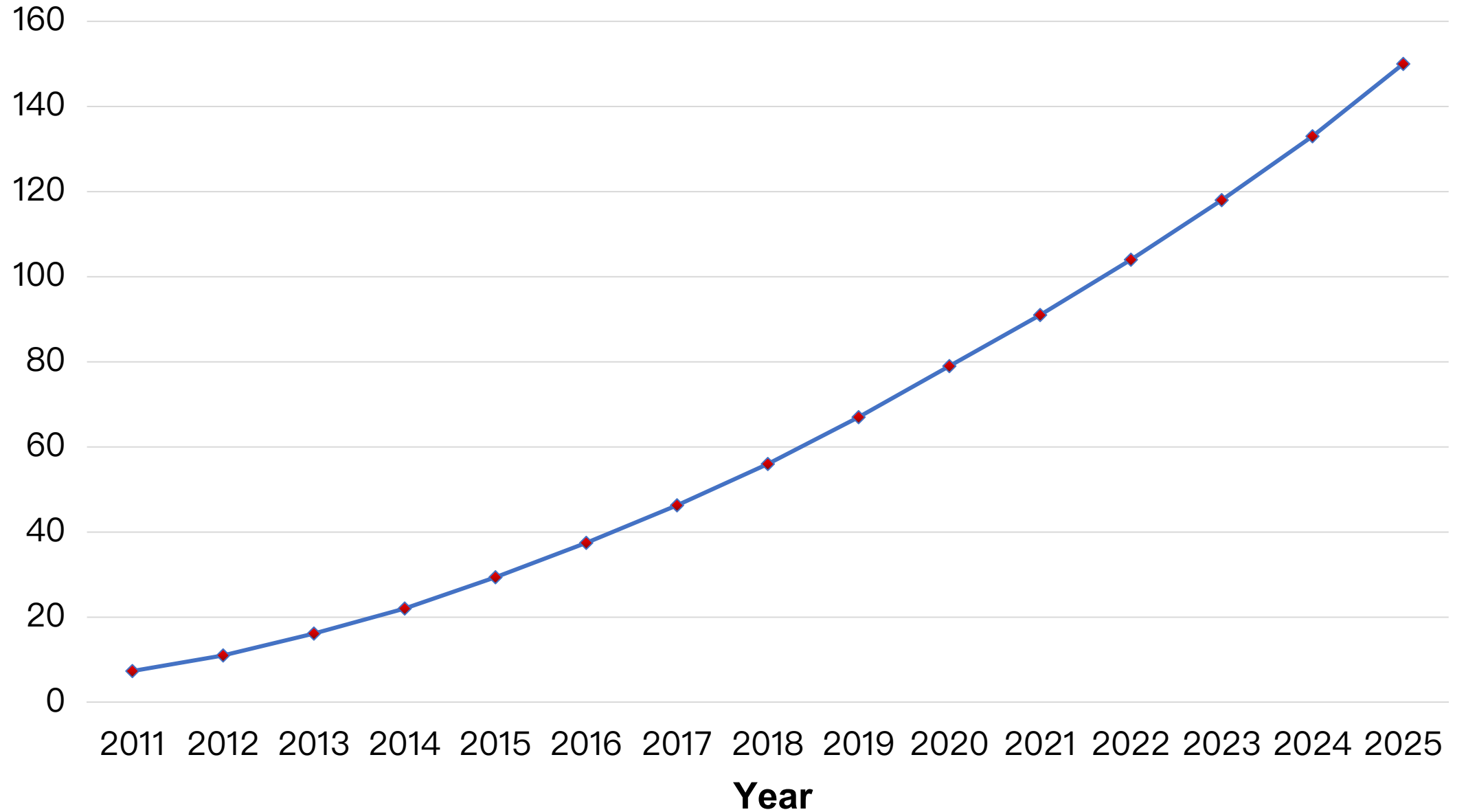
DW Linear Speed of Slicer During Cutting

m/s



Monthly Output Per Slicer, M10 Equivalent Mono-Crystal Silicon Wafer

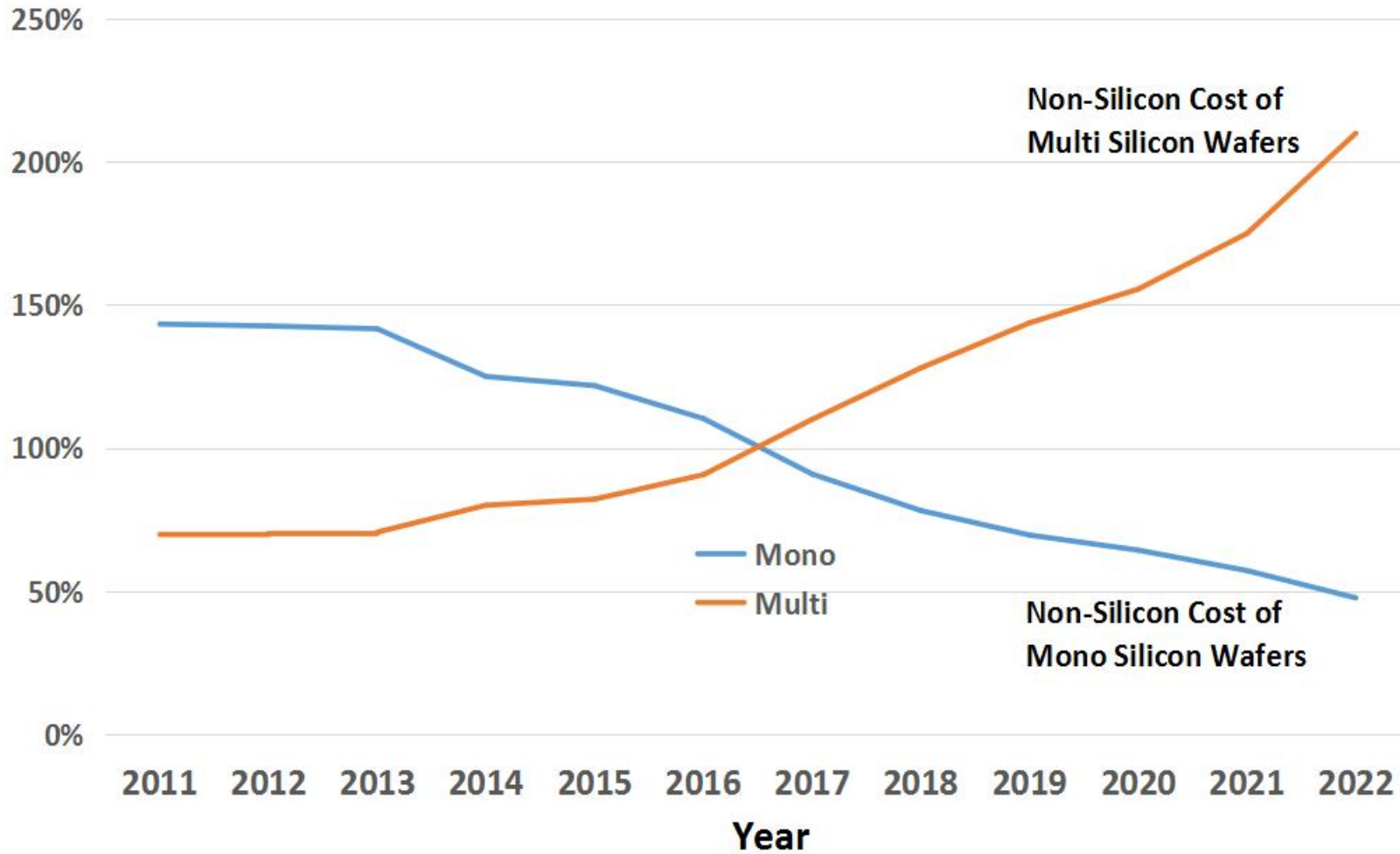
10K Wafer



Trend of Non-Silicon Cost, Mono vs. Multi Silicon Wafers

单晶硅片和多晶硅片非硅成本趋势（相对比例）

Relative Percentage



Trend of Market Share Mono vs. Multi Silicon Wafers (Multi including Cast Mono)

Mono
Multi



To become a strong player in PV industry, it is very important to select the right technical path. Linton made 3 critical decisions in the past 15 years:

Third critical decision:

Being the first to promote factory automation of ingot/wafer production lines while most people in PV industry believed automation is too expensive and not necessary

Crystal Growth Process Automation

Current status:

- From seed dipping to tailing: fully automated

Pump Down	Stabilizing
Seed dipping	Crowning
Body Growth	Tailing
Cooling	Recharging

- Growth speed and productivity:

9 inch crystal (M6):

Speed >2.0mm/min,

Productivity>150kg/day

10 inch crystal (M10):

Speed >1.9mm/min,

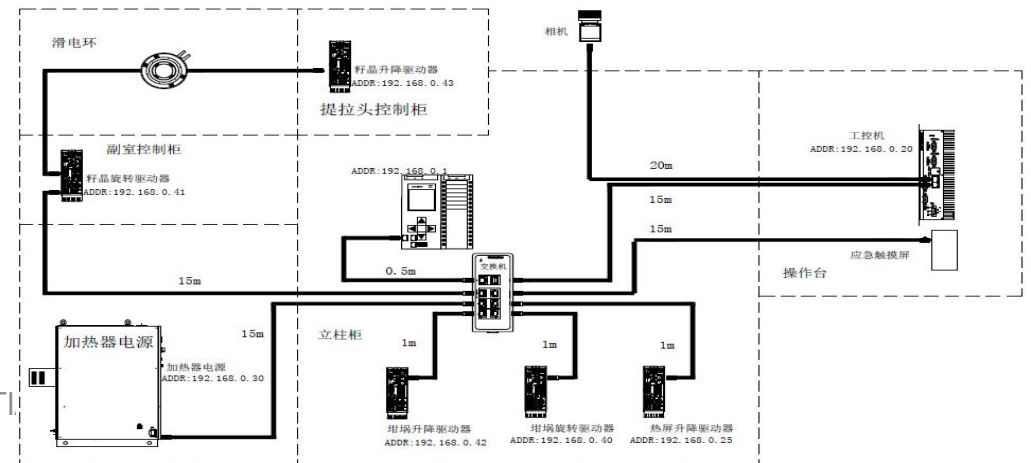
Productivity>150kg/day

12 inch crystal (G12):

Speed >1.7mm/min,

Productivity>170kg/day

- Loss of structure less than 25 per 100 pulls

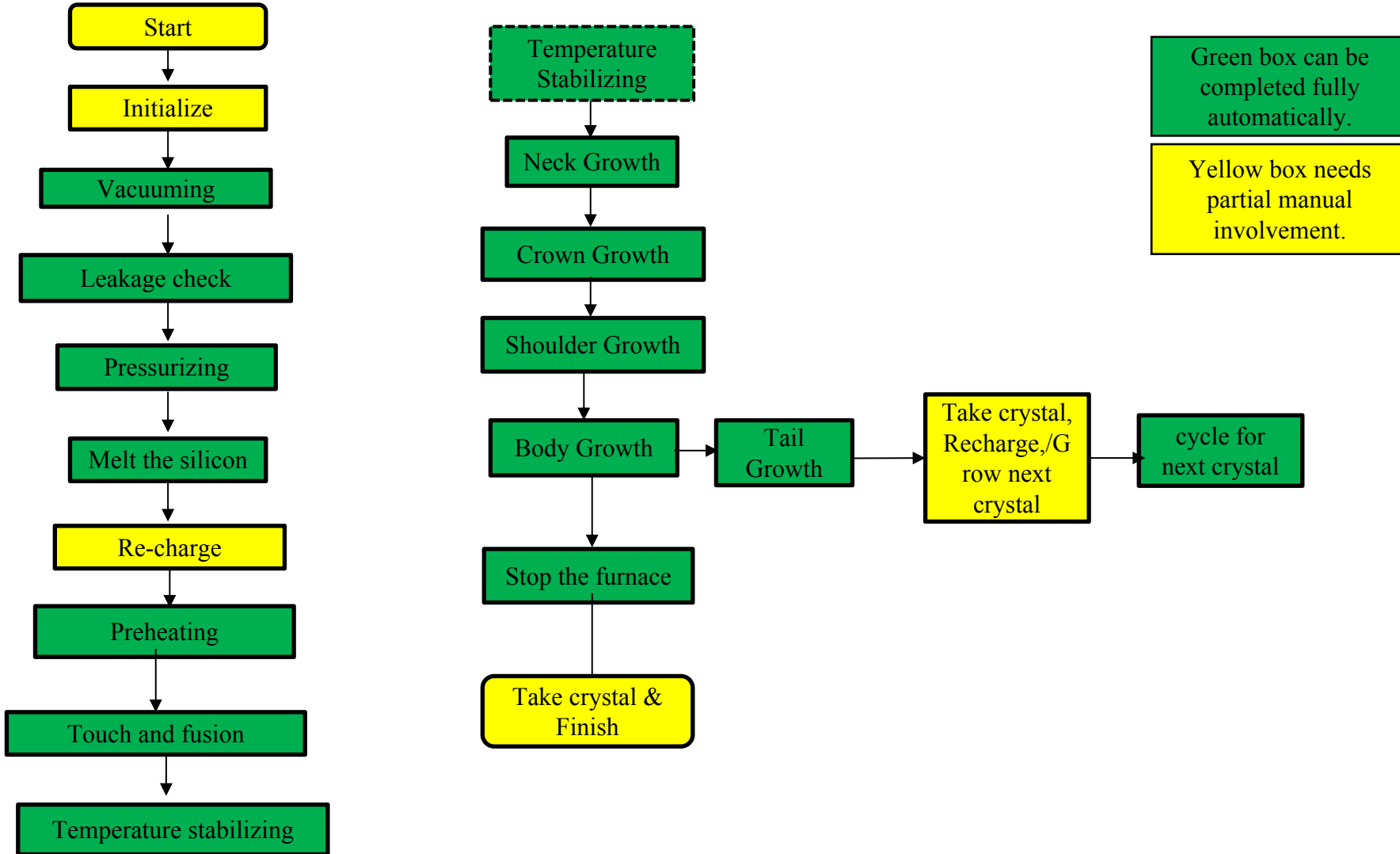


COMPANY CONFIDENTIAL

"One-click crystal growth"- Procedure

Full process automation from vacuuming to tail

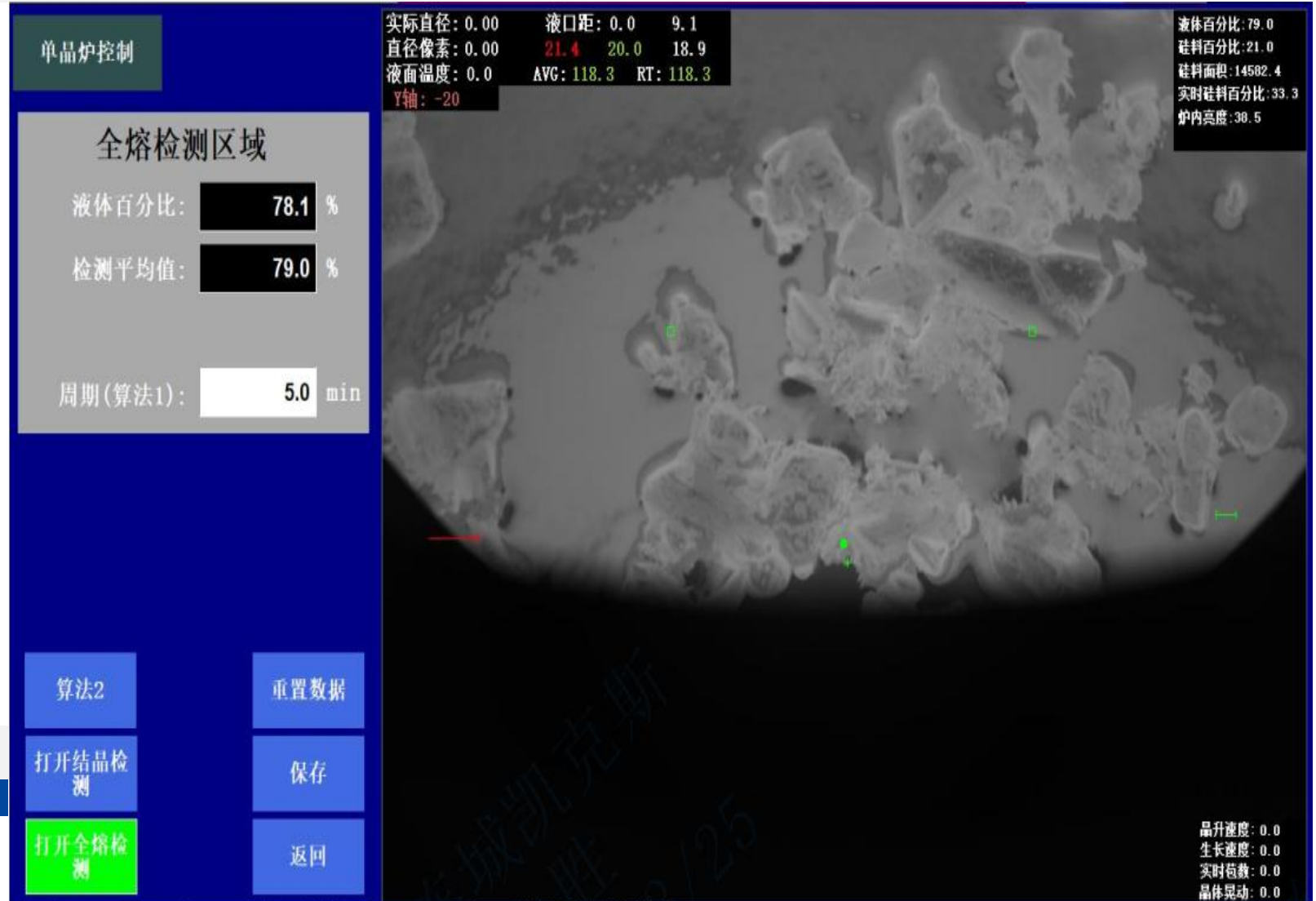
Monocrystal Production
Intelligentization



“One-click crystal growth”- Molten poly silicon percentage detection by CCD

The data from molten poly silicon percentage detection is important for:

1. Deciding the time of poly silicon re-charging;
2. Automatic setting of heater power for melting;
3. Predicting the start point of following processes.



"One-click crystal growth" : Automatic temperature stabilizing

1. Melt surface temperature measurement using CCD camera;
2. Automatic adjustment of heater power;
3. Automatic judgement of completion of temperature stabilizing.

The screenshot displays the control interface for a crystal growth system. The top bar includes the status '调温' (Temperature Control), a clock '60:34', the mode '相机-引晶模式' (Camera-Crystal Growth Mode), the time '16:39:37', and an '紧急保护按钮' (Emergency Protection Button).

The main control panel is titled '单晶炉控制' (Single Crystal Furnace Control) and features a '晶点检测区域' (Crystal Point Detection Area) section with the following parameters:

- 检测周期 (min): 1.0
- 检测阈值: 0.0
- 检测频率: 8.0
- 上周期晶点计数: 0
- 本周期晶点计数: 0
- 判定可用点数: 40.0
- 晶点检测OK阈值: 0.45
- 短滤波长度: 50

At the bottom of the control panel are buttons for '算法切换' (Algorithm Switch), '保存' (Save), '打开检测' (Open Detection), and '返回' (Return).

The central area shows a live camera feed of the crystal growth process. The feed includes a green rectangular detection area and a central crosshair. The top of the feed displays real-time data: '实际直径: 10.03', '液口距: 35.4 34.0', '直径像素: 95.58 70.4 70.8 70.8', '液面温度: 1450.4 AVG: 51.0 RT: 51.5', and 'Y轴: 50'. The right side of the feed shows '上期晶点数: 0.0', '本期晶点数: 0.0', '是否发现晶点: False', '晶点占比(短): 0.34', '晶点占比(长): 0.13', and '晶点突出程度: 5.00'. The bottom right corner of the feed shows '晶升速度: 0.0', '生长速度: 0.0', '实时苞数: 0.0', and '晶体晃动: 0.0'.

"One-click crystal growth" : Automatic seed touching and fusion

1. Automatic preheat the seed;
2. Automatic detection of seed position;
3. Automatic adjustment of heater power;
4. Automatic seed touching and fusion completion.

预热/熔接 00:02 相机-空闲模式 15:39:06 紧急保护按钮

实际直径: 300.59 液口距: 34.6 33.2
 直径像素: 0.00 70.2 69.5 69.3
 液面温度: 1461.6 AVG: 62.1 RT: 62.0
 Y轴: 50

单晶炉控制

空闲模式	引晶模式	放肩模式
等径模式	等径液口距关	等径液口距开
相机调节1	安全保护液距	相机调节2
扫描区域1	籽晶检测	扫描区域2
液口距-小	液口距-大	导流筒面积
断线检测	温度设置	品点检测
全熔检测	H线-设置	锁定
晶见检测	X线1	X线2
导流筒标定	缩放1	缩放2

籽晶长度: 400.9
 籽晶检测状态: True
 接触检测: False

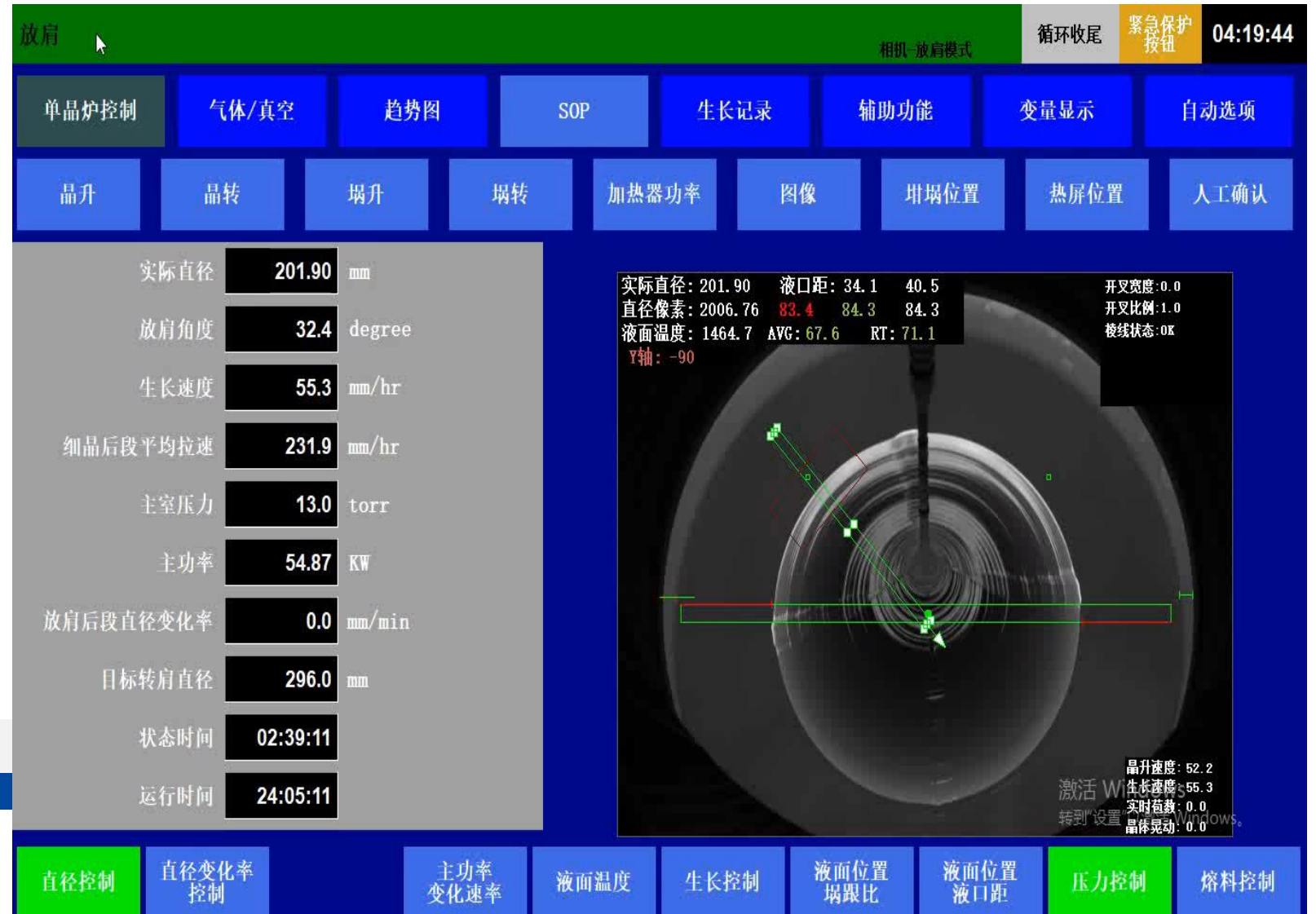
晶升速度: 0.0
 生长速度: 0.0
 实时苞数: 0.0
 晶体晃动: 0.0

"One-click crystal growth" : Automatic crown growth

Fully automatic crystal crown growth with preset crown shape curvature.

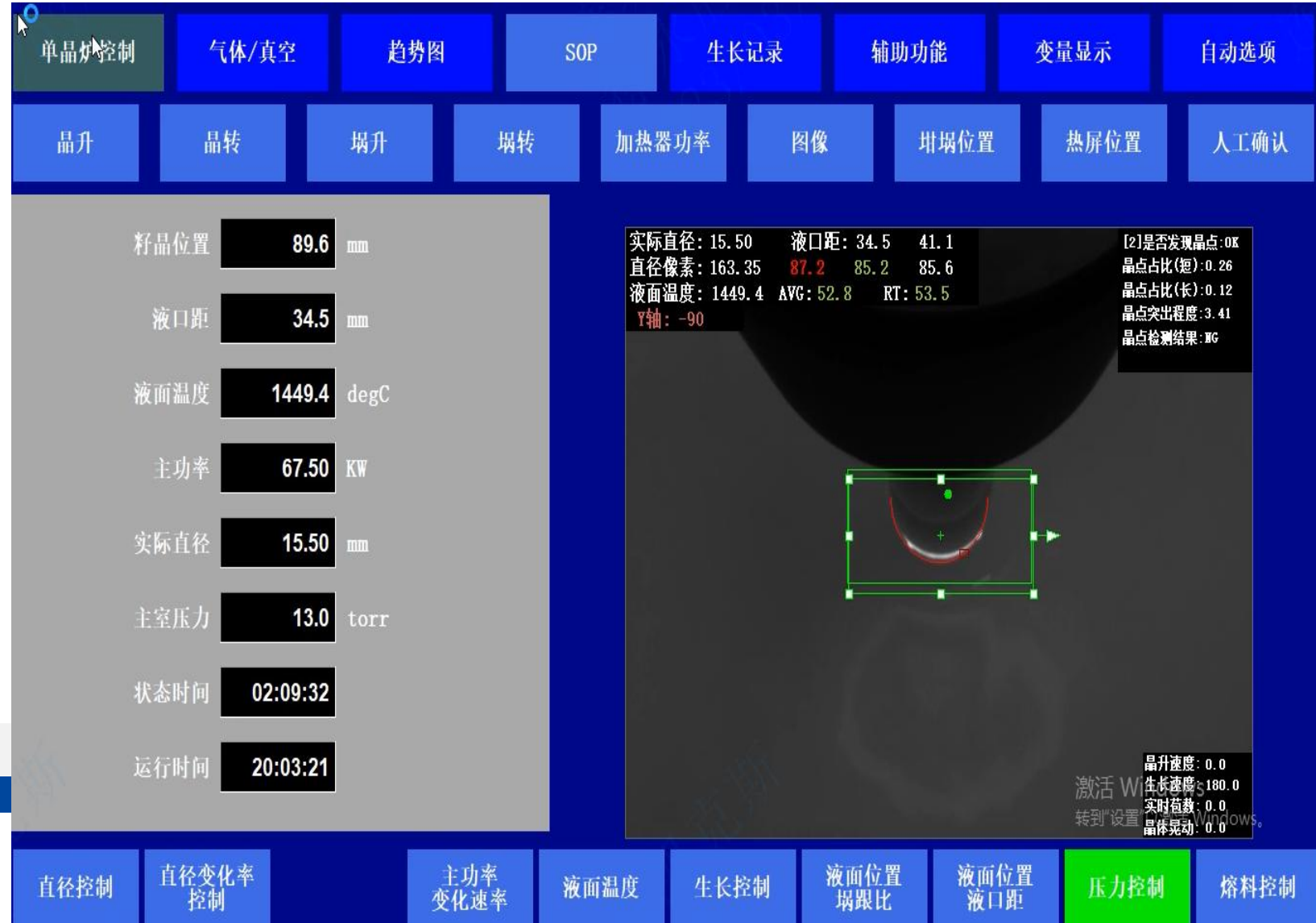
Has facet examination function to decide whether the crystal is in good condition.

Self-learning AI algorithm to gradually improve success rate.



"One-click crystal growth" : Facet detection by CCD at start point of growth

During temperature stabilizing, using CCD to check the size and condition of facet points at the seed/melt interface to decide whether the temperature of the melt is proper for starting the neck growth. Because the facet points are very small, highly accurate CCD system and sophisticated algorithms are needed for this step.



Curve fitting method for diameter calculation

Coordinate positions of multiple points along the meniscus are measured and commercial algorithms are used to calculate the diameter

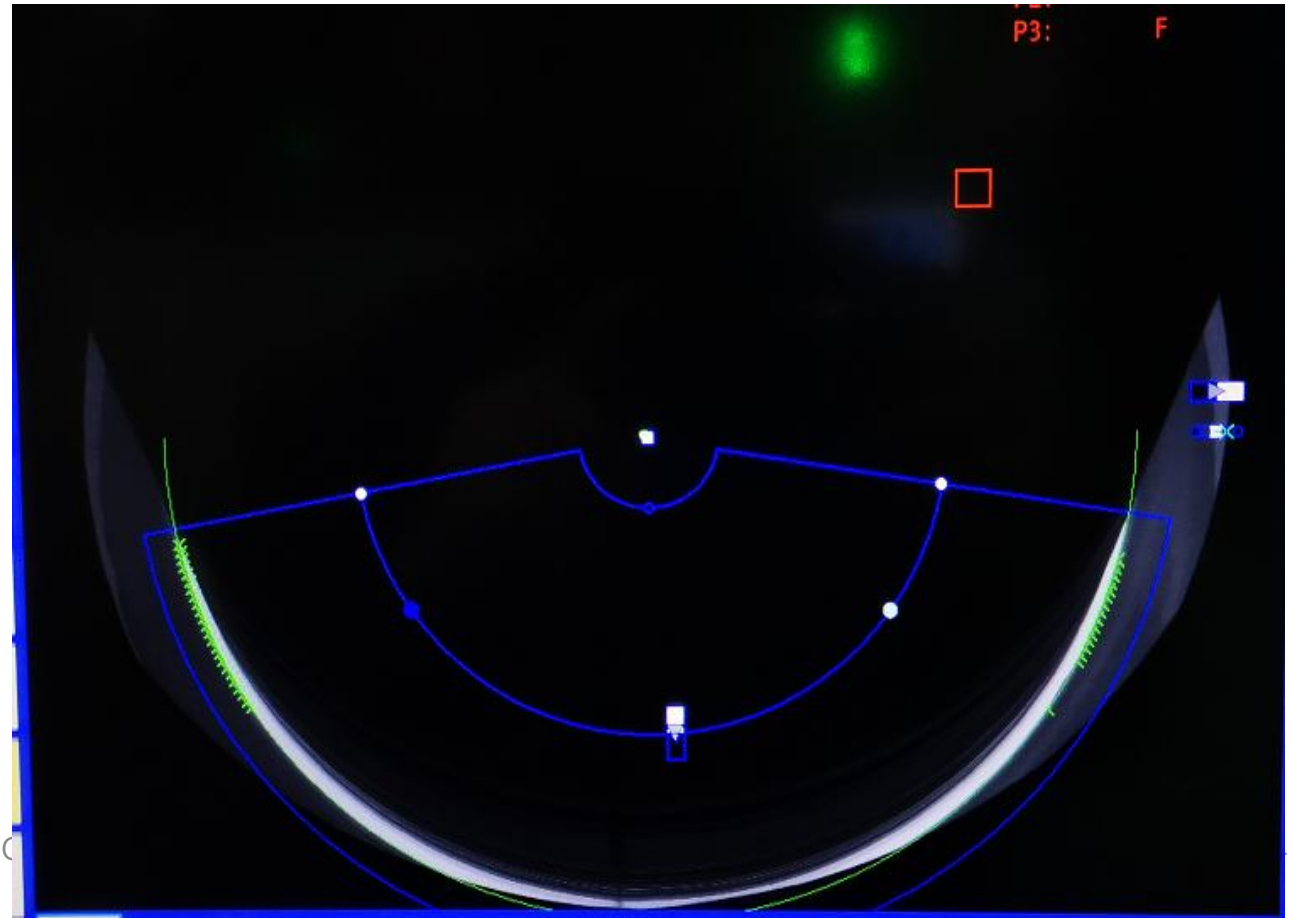
Again, because CCD is doing measurement at an angle, the value of R is dependent on melt surface position. Accurate melt surface position measurement is needed for a high accuracy crystal diameter measurement

Disturbances such as crystal movement and melt surface wave affects diameter measurement accuracy

Question:

How to accurately measure the melt surface position ?

Melt surface position is also called Melt Level

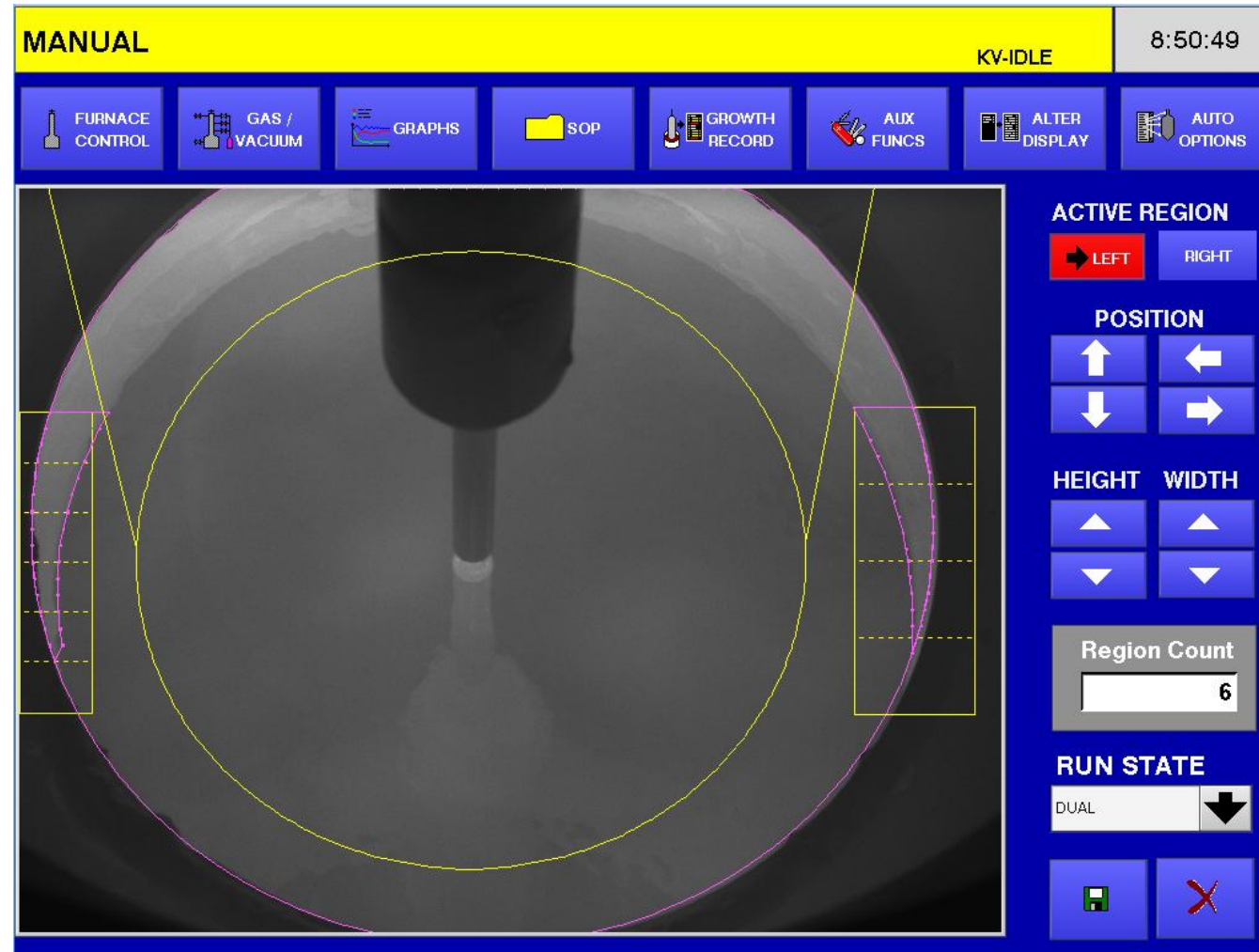


"One-click crystal growth" : Melt Gap measurement

Using CCD camera to capture the image of heat shield bottom edge and its reflection inside the melt, then calculate Melt Gap through Geometric relationship.

Accurate measurement of melt gap is critical in determining automated growth speed of the crystal.

Melt surface waves, color change of melt, dimensional accuracy of components, etc. , affect measurement accuracy of MG. Thus Advanced tech is needed



Centralized control system - classified display



分类显示

全部	80
手动	9
熔料	1
预热/熔接	2
调温	3
引晶	1
放肩	5
等径	43
收尾	2
渣盖提出	0
副室净化	1
隔离	0
晶体冷却提出	0
料筒提入	1
料筒提出	1
试验炉台	0

首页 上一页 1 4 下一页 尾页 配置

设备D61

直径: 251.61 2523.23 液口距: 23.2 0.0
Y轴: 92 49.1 49.9 50.2

设备D63

直径: 250.51 2504.08 液口距: 16.9 0.0
Y轴: 92 39.2 40.7 40.3

设备D67

直径: 251.39 2475.49 液口距: 22.1 0.0
Y轴: 92 51.8 50.7 50.8

设备D69

直径: 251.24 2502.86 液口距: 17.2 0.0
Y轴: 92 42.5 40.9 40.8

设备D71

直径: 251.05 2492.11 液口距: 17.1 0.0
Y轴: 92 40.7 41.9 42.0

设备D73

直径: 250.86 2496.41 液口距: 16.8 0.0
Y轴: 92 37.9 37.6 37.3

设备D75

直径: 250.76 2446.52 液口距: 37.0 0.0
Y轴: 92 85.1 83.0 83.4

设备D77

直径: 250.68 2495.48 液口距: 17.4 0.0
Y轴: 92 89.6 38.5 38.3

设备D79

直径: 251.13 2497.34 液口距: 16.8 0.0
Y轴: 92 44.7 43.3 43.3

设备D81

直径: 251.38 2450.12 液口距: 17.4 0.0
Y轴: 92 34.3 34.1 33.9

设备D82

直径: 301.67 2990.28 液口距: 37.5 0.0
Y轴: 92 85.3 82.5 81.7

设备D83

直径: 250.55 2488.19 液口距: 17.1 0.0
Y轴: 92 37.9 40.5 40.6

Classified display

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New Directions:

- 1. Using Artificial Intelligence in crystal growth, wafer slicing & ingot/wafer factory;***
- 2. Achieving lower oxygen, lower cost; higher productivity, higher quality;***
- 3. Full ingot/wafer production line integration and automation.***

New Generation Advanced N-Type Smart Crystal Puller KX420 Series

1. Lower Cost, Higher Yield

- Up to 200+kg/day per puller yield.
- Lower hot zone power consumption, body growth power can be as low as 42 kW.
- Lower water consumption, cooling water flow rate per puller can be as low as 20m³ /h.

2. Higher Quality

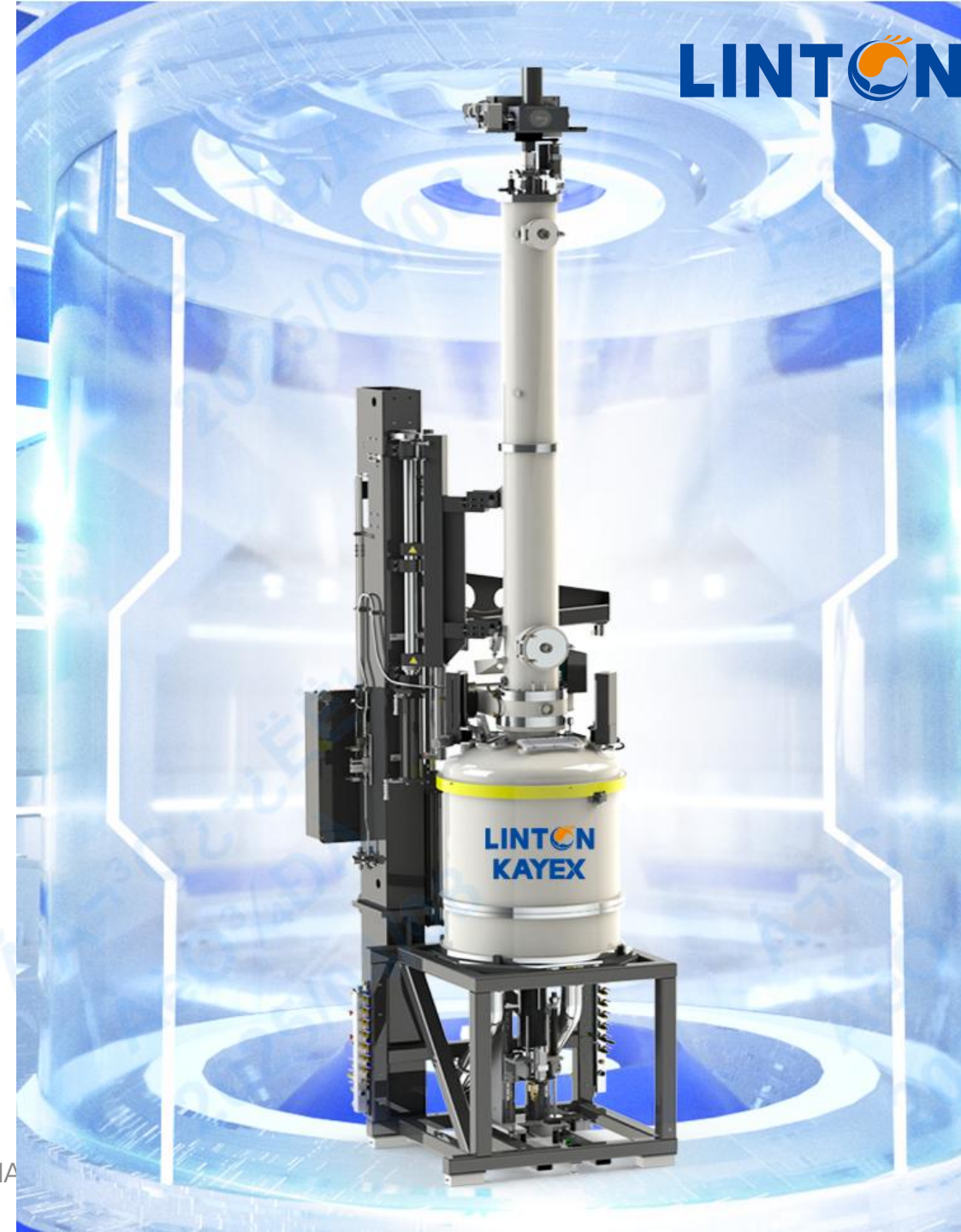
- Multiple oxygen control schemes and configurations, ingot oxygen concentration can be as low as 6 PPM.
- More uniform resistivity and higher minority carrier lifetime.

3. Broader Compatibility

- Hot zone diameter up to 42 inches, ingot diameter up to 16 inches.
- Compatible with CCz and magnetic field.

4. Smart Ingot Growth

- Integrated BI and AI based on big data of equipment and optimized whole process flow.



Type	Model	Chamber (mm)	Throat (mm)	Receiving chamber (mm)	Upper bearing load (Kg)	Lower bearing load (Kg)	Total equipment weight	Crucible loading capacity	Crucible diameter				
									33 in.	37 in.	40 in.	42 in.	44 in.
1600+	KX380PV	φ1600*2050	φ410	φ410*5500	1500	2000	≈16 tons	Loading capacity	700kg	1000kg	1200kg	/	/
1700	KX420PV	φ1700*2100	φ450	φ450*5500	1500	2000	≈17 tons		700kg	1000kg	1200kg	1400kg	/
1800	KX460PV	φ1800*2100	φ450	φ450*5500	1500	2000	≈17 tons		700kg	1000kg	1200kg	1400kg	1450kg

Type	Delivery	Max hot zone compatibility	Puller type dimension compatibility	Product description	Standard Configuration	Optional Configuration
1600+	The first in the industry to develop and deliver over 8,000 units in bulk.	40 in.	Compatible with 1700 equipment factory layout.	Meets the demand for larger feeding capacity and larger-spec crystal rod growth, with multiple upgradeable modules reserved for cost-effective technological upgrades. The 1700 and 1800 models can meet the growth requirements for 16-inch crystal rods.	1.One-click Crystal Pulling Module 2.Centralized Control System 3.Low Oxygen Crystal Pulling Power Supply 4.High-efficiency Heating 5.High-speed Vacuum Pump 6.High-efficiency Filtration Tank;	1.Data Center & Big Data Analysis System Vision Server 2.Monocrystalline Production MES System 3.Low Oxygen Crystal Pulling Module 2.0 4.Extension Chamber 5.CCz Process Equipment 6.MCz/MCCz Magnetic Field Solution 7.High-efficiency Thermal Field Process Package 8.Production Auxiliary Tools
1700	The first in the industry to develop and deliver over 2,000 units in bulk.	42 in.	Compatible with 1600+ equipment factory layout.			
1800	/	44 in.	/			

Technological Leadership:

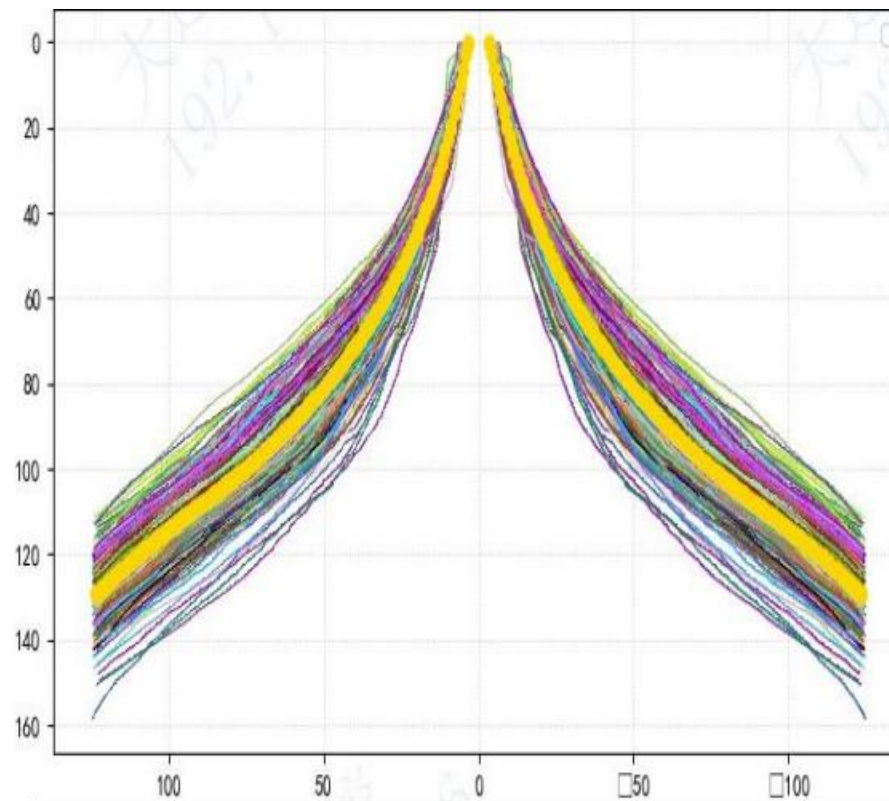
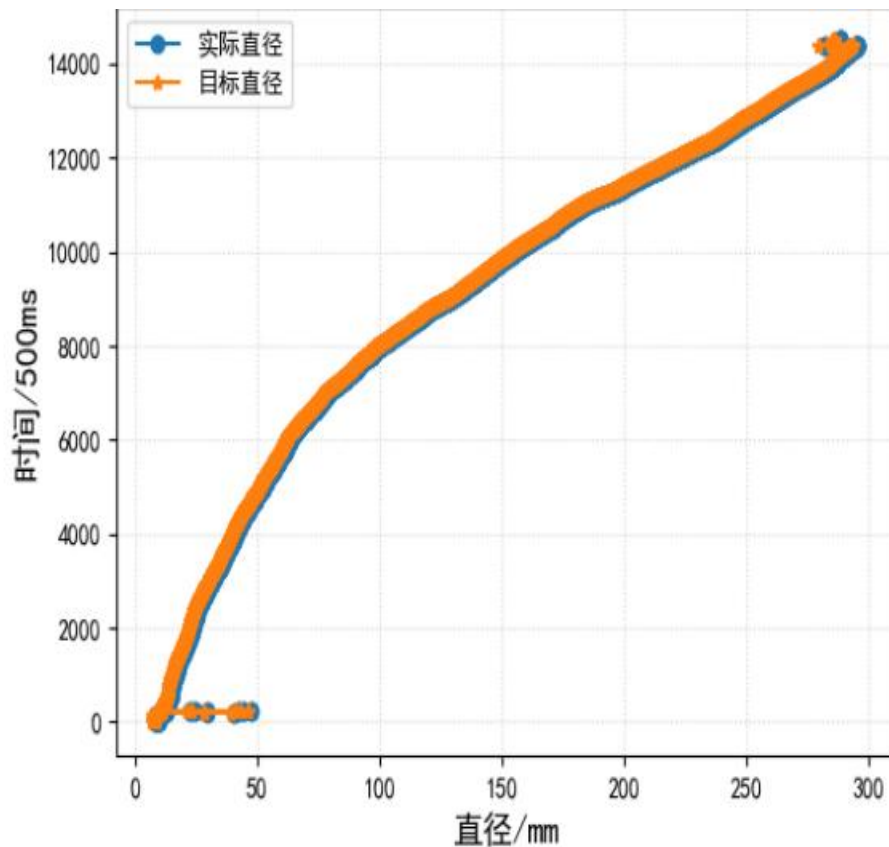
- 1.Equipped with the next-generation digital intelligence platform, daily output increased by 10kg+/day, leading the industry.
- 2.Lower hot zone power consumption, with isothermal power reduction exceeding 10%, leading the industry.
- 3.Reduced water usage, with cooling water flow as low as 20m³/h.
- 4.Multiple oxygen control solutions and configurations available, as low as 6PPM, ensuring more uniform resistivity and longer minority carrier lifetime.
- 5.Maximum thermal field size of 44 inches, with a maximum silicon rod diameter of 16 inches, compatible with CCz and magnetic fields.

Intelligent Crystal Pulling:

- 1.Integration of BI and AI based on equipment big data to optimize the entire process flow.
- 2.Intelligent crystal pulling with full process automation, automatically recommending pulling power and achieving an automatic pulling and releasing accuracy rate of ≥99%.
- 3.AI-based visual inspection and automatic crucible release modules with improved accuracy, stability, and safety, offering customers higher automation rates and unmanned operation efficiency.



" One-Click Crystal Pulling" : AI intelligent shoulder growing



Intelligent prediction of growth trends, automatic intervention in crystal growth
Crystal success rate increased > 7%, Production yield increased > 3%

New: Linton Advanced N-Type Ultra-Thin Wafer Slicer

Comprehensive advantages:

- Ultra-thin wires, 16–18 μ m
- Ultra-thin wafer, 45–50 μ m
- Large loading capacity, up to 1000mm brick length
- Higher yield, > 96.5%
- Lower wire consumption, save 20–30%
- High wire speed, 45m/sec
- User-friendly operation
- Compatible with wafers of all different sizes: 182/210/Half
- Automatic operation features
- Process improvement with AI

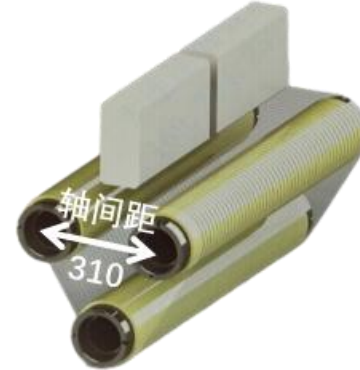


Progress in Slicing Technology - QP950 Slicer for Ultra-thin N-Type Silicon Wafers: M10/G12 Half-Wafer & Full-Wafer Capable

Adjustable wheelbase for optimal slicing condition. Ideal for fine wire and ultra-thin wafer.



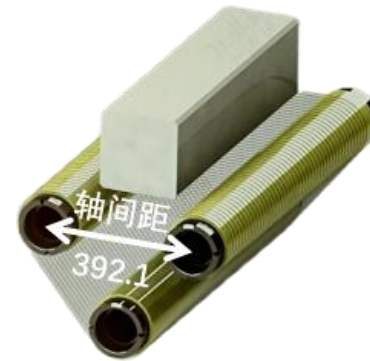
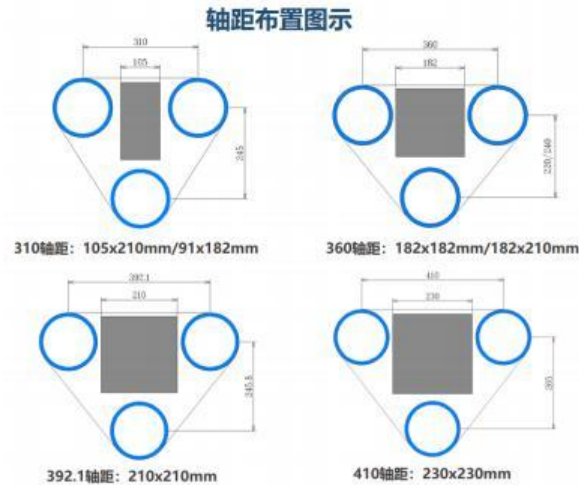
Half-Wafer: finished specifications 210x105mm, axle spacing is 310mm, and finished wafer thickness can be ~ 45μm.

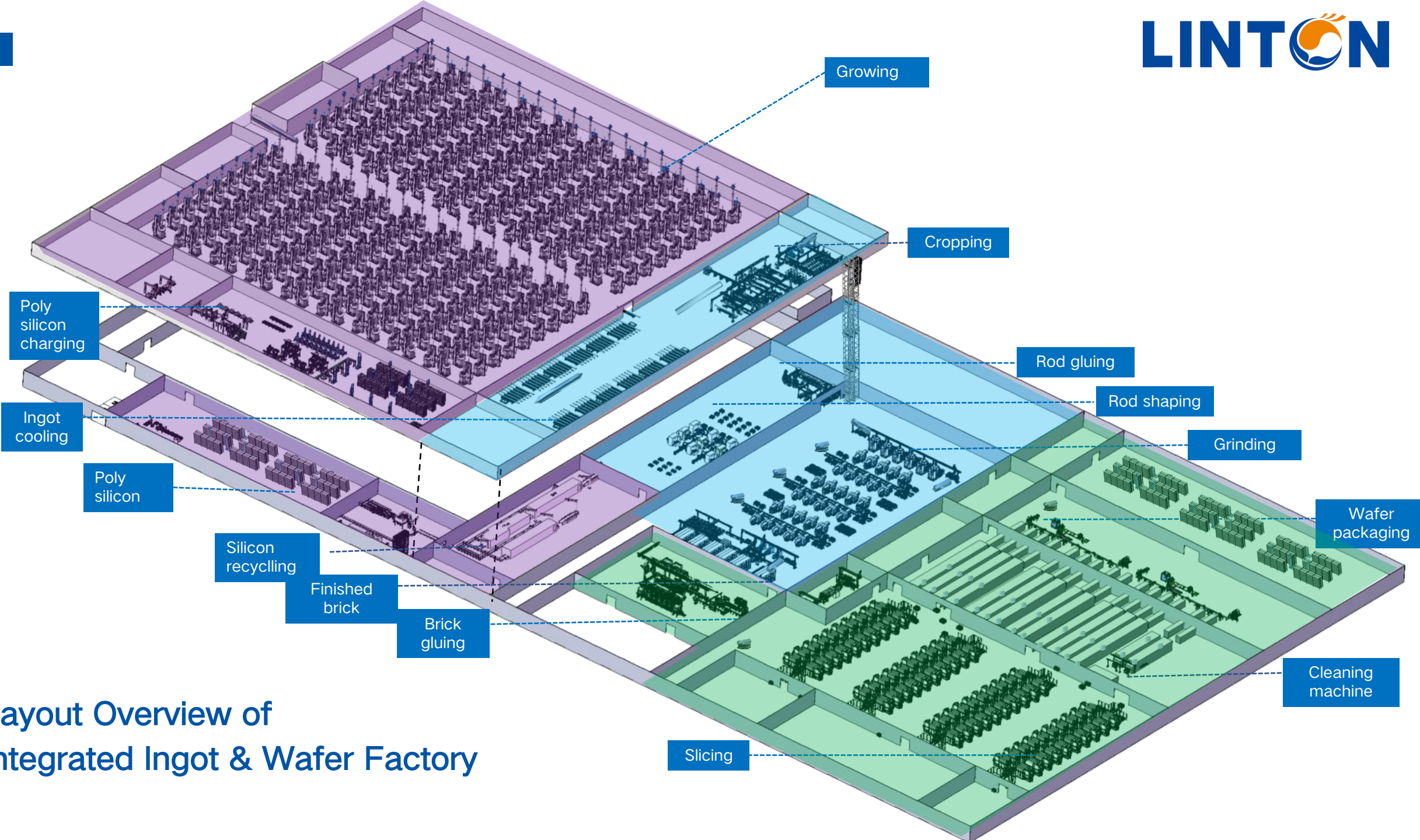


Full-Wafer: finished specifications 210x210mm, axle spacing is 392.1mm, and finished wafer thickness can be ~ 55μm.

Highly flexible design, all three axes' wheelbases are adjustable.

Maintaining optimal horizontal and vertical axis spacing for different wafer specifications, ensuring cutting capability



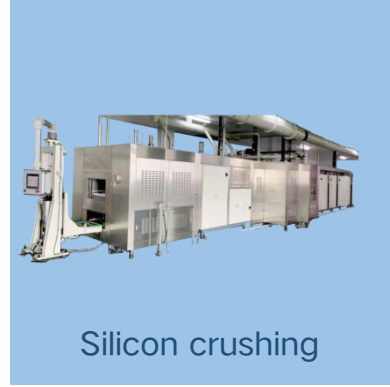


Layout Overview of Integrated Ingot & Wafer Factory

Ingot-wafer Smart Factory Solution – One Station Service by Linton



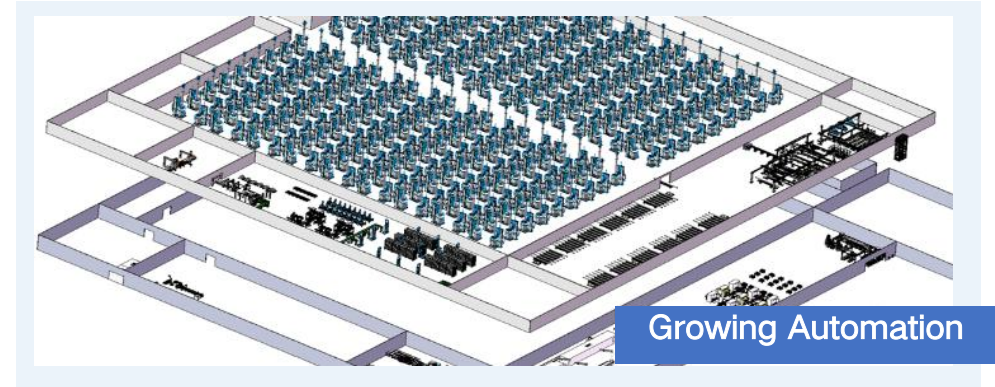
Silicon cleaning



Silicon crushing



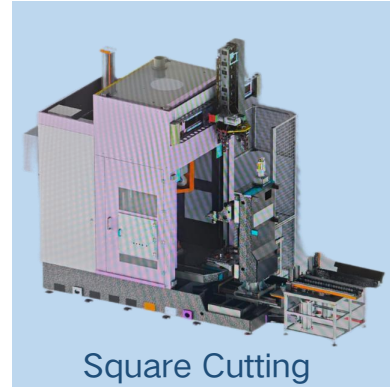
Ingot growing



Growing Automation



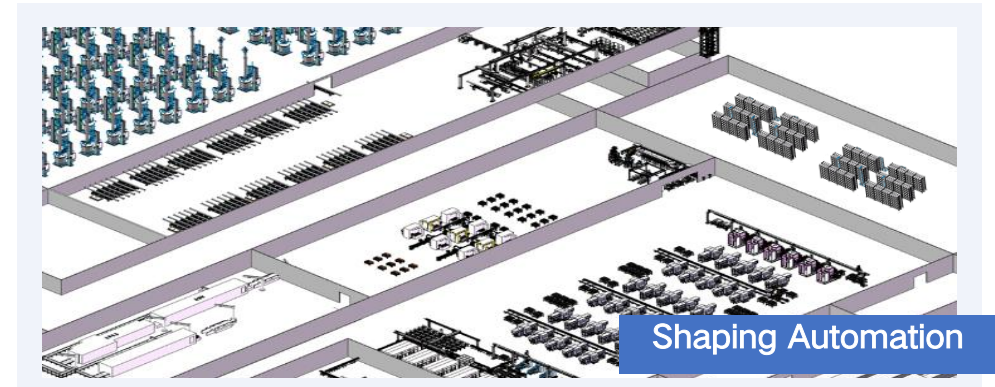
Ingot cropping



Square Cutting



Grinding



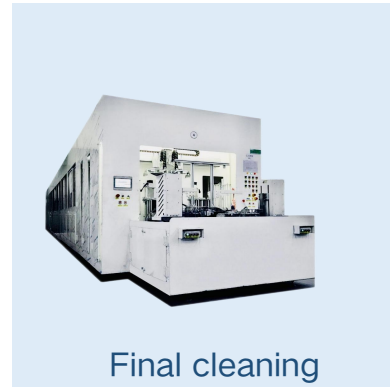
Shaping Automation



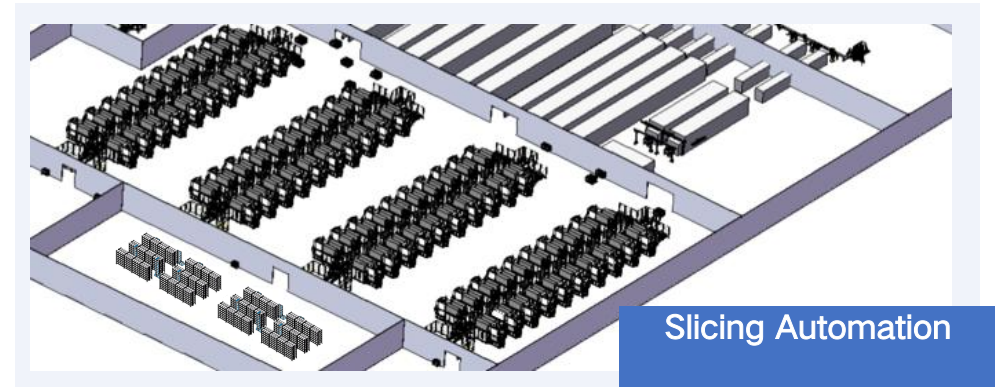
Slicing



Wafer degluing



Final cleaning



Slicing Automation

10GW Ingot & Wafer Factory

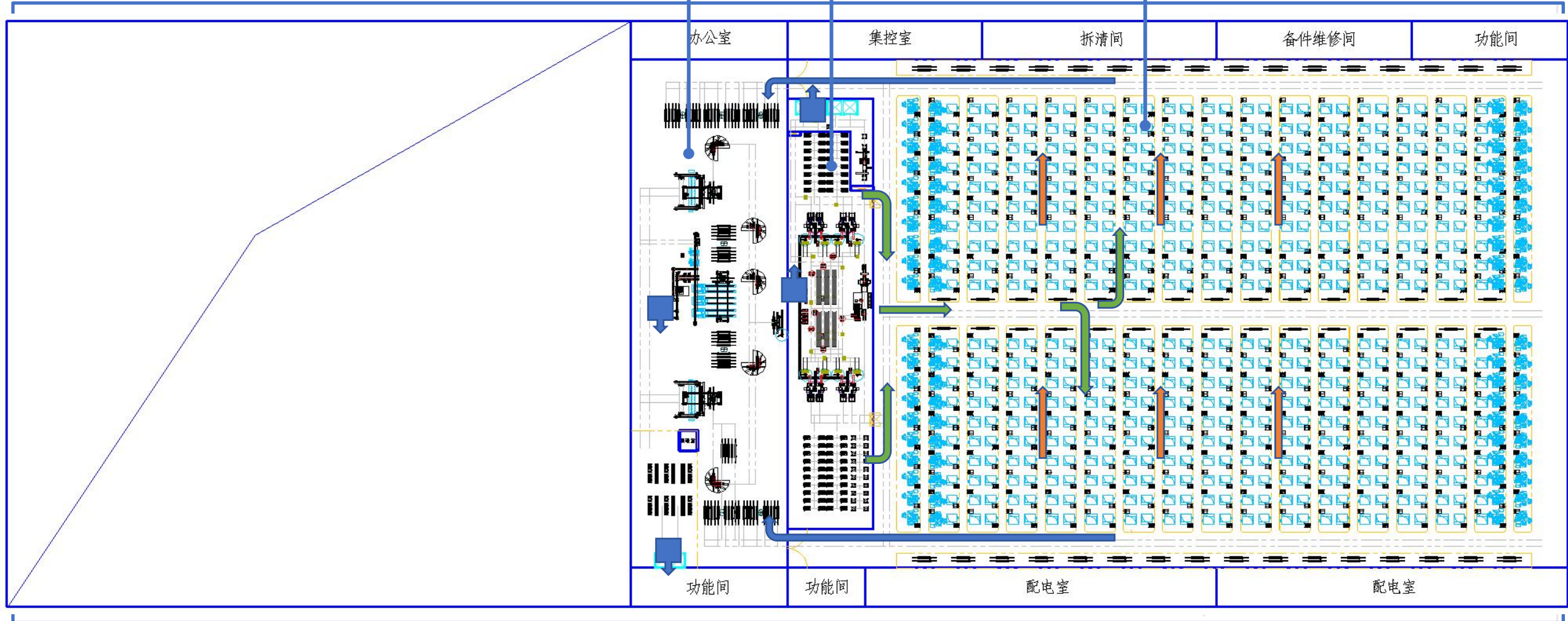
2F

2F

Cropping Area

Poly-Silicon Charging Area

Grower Area



Ingot & Recycle Mat. Down

Raw Material Up

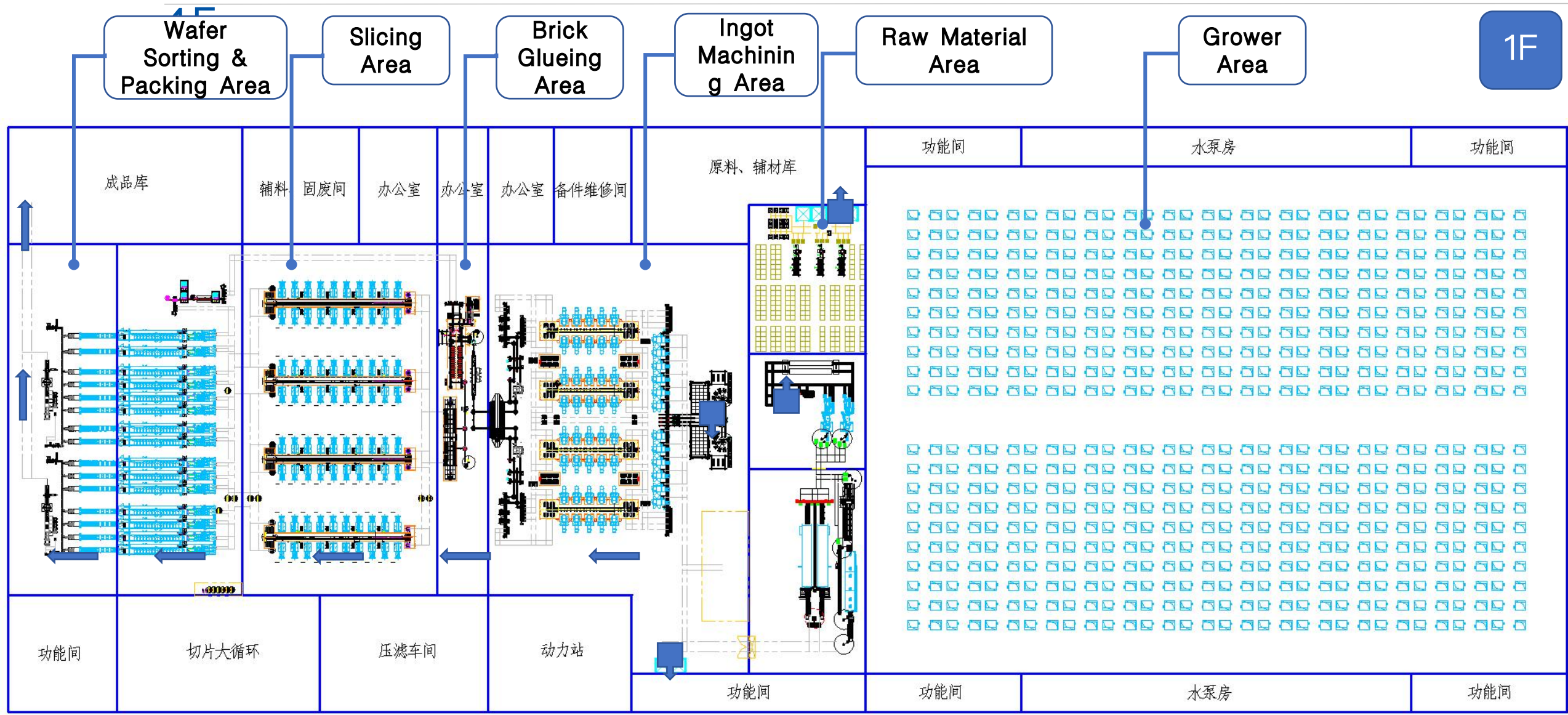
Ingot Transport

Crucible & Hopper Transport

Hot Zone Transport

10GW Ingot & Wafer Factory

1F



Ingot & Recycle Mat. Down

Raw Material Up

Material Flow

银川隆基光伏示范项目

生产任务完成情况

2226
1812
1604

50%

60%

50%

生产任务完工情况看板

生产任务完成率

生产任务完成率

日期	计划	实际	完成率
10/1	100	100	100%
10/2	100	100	100%
10/3	100	100	100%
10/4	100	100	100%
10/5	100	100	100%
10/6	100	100	100%
10/7	100	100	100%
10/8	100	100	100%
10/9	100	100	100%
10/10	100	100	100%

工时看板

负责人	班组	设备	开始时间	设备	结束时间
王二	二班	设备1	10:00:00	设备1	10:15:47
王二	二班	设备2	10:00:00	设备2	10:15:47
王二	二班	设备3	10:00:00	设备3	10:15:47
王二	二班	设备4	10:00:00	设备4	10:15:47
王二	二班	设备5	10:00:00	设备5	10:15:47
王二	二班	设备6	10:00:00	设备6	10:15:47
王二	二班	设备7	10:00:00	设备7	10:15:47
王二	二班	设备8	10:00:00	设备8	10:15:47
王二	二班	设备9	10:00:00	设备9	10:15:47
王二	二班	设备10	10:00:00	设备10	10:15:47

异常信息通知看板

时间	炉号	异常原因	责任人
10/1 10:00	1001	设备异常	王二
10/1 10:05	1002	无异常	王二
10/1 10:10	1003	无异常	王二
10/1 10:15	1004	设备异常	王二
10/1 10:20	1005	无异常	王二
10/1 10:25	1006	设备异常	王二
10/1 10:30	1007	无异常	王二
10/1 10:35	1008	设备异常	王二
10/1 10:40	1009	无异常	王二
10/1 10:45	1010	设备异常	王二

工作任务达成情况看板

2019.08.27 10:01

负责人	班组	设备	开始时间	设备	结束时间
王二	二班	设备1	10:00:00	设备1	10:15:47
王二	二班	设备2	10:00:00	设备2	10:15:47
王二	二班	设备3	10:00:00	设备3	10:15:47
王二	二班	设备4	10:00:00	设备4	10:15:47
王二	二班	设备5	10:00:00	设备5	10:15:47
王二	二班	设备6	10:00:00	设备6	10:15:47
王二	二班	设备7	10:00:00	设备7	10:15:47
王二	二班	设备8	10:00:00	设备8	10:15:47
王二	二班	设备9	10:00:00	设备9	10:15:47
王二	二班	设备10	10:00:00	设备10	10:15:47

工作任务达成情况看板

2019.08.27 10:01

设备	计划	实际	完成率
设备1	10	10	100%
设备2	10	10	100%
设备3	10	10	100%
设备4	10	10	100%
设备5	10	10	100%
设备6	10	10	100%
设备7	10	10	100%
设备8	10	10	100%
设备9	10	10	100%
设备10	10	10	100%

人员管理看板

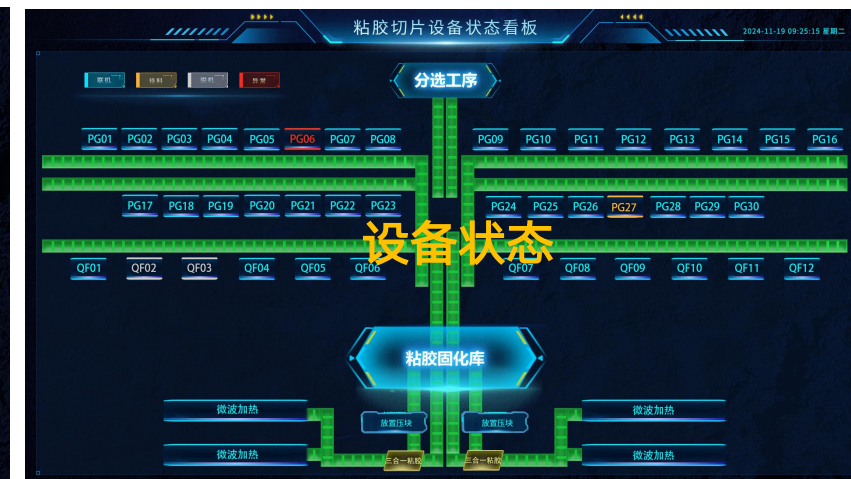
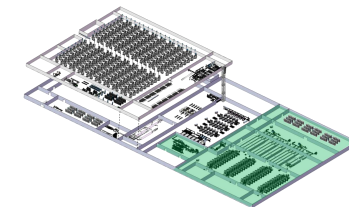
名次	姓名	班组	引导效率	调温时间
1	王二	001	5h	0.2h
2	王二	001	3.2h	1.3h
3	王二	001	3.2h	1.3h
4	王二	001	3.2h	1.3h
5	王二	001	4.2h	5h
6	王二	001	3.2h	1.3h
7	王二	001	5h	0.5h
8	王二	001	3.2h	1.3h
9	王二	001	4.9h	5h
10	王二	001	4.9h	5h

异常信息通知看板

2019.08.27 15:15

时间	炉号	异常原因	责任人
10/1 10:00	1001	设备异常	王二
10/1 10:05	1002	无异常	王二
10/1 10:10	1003	无异常	王二
10/1 10:15	1004	设备异常	王二
10/1 10:20	1005	无异常	王二
10/1 10:25	1006	设备异常	王二
10/1 10:30	1007	无异常	王二
10/1 10:35	1008	设备异常	王二
10/1 10:40	1009	无异常	王二
10/1 10:45	1010	设备异常	王二

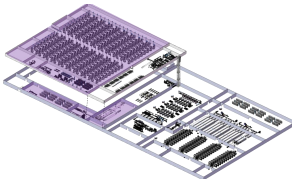
Digitization of the slicing workshop





Central Control Room

Smart Factory, Digitalized Central Control Platform





An aerial photograph of a large-scale renewable energy project. The foreground and middle ground are dominated by a vast solar farm with rows of photovoltaic panels installed on a sloping, green hillside. In the background, several white wind turbines are scattered across the ridge. The landscape is lush with green trees and vegetation. In the distance, a coastline with buildings and a body of water is visible under a bright, hazy sky with some clouds. The overall scene conveys a message of clean, sustainable energy production in a natural setting.

Thank you!

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